

ABSTRACT OF THE DISCLOSURE

A resist composition comprising:

(A) a compound capable of generating an active seed upon irradiation with one of an actinic ray and a radiation,

(B) a compound capable of reacting with the active seed generated from the compound (A) and/or performing electron transfer to generate an active seed different from the active seed generated from the compound (A), and

(C) a compound capable of performing electron transfer from the active seed generated from the compound (B) to generate an acid,

wherein supposing that the 1/2 wave of the oxidation potential of the active seed generated from the compound (B) is E_{pa} and the 1/2 wave of the reduction potential of the active seed generated from the compound (C) is E_{pc} , the relationship: $E_{pc} - E_{pa} > 0$ is satisfied.